

Amendments to the Claims

1. (Original) An LCD device having an input line part comprising:
 - a first line layer formed on a substrate;
 - a first insulating layer formed on the substrate, having a contact hole therein located at the first line layer;
 - a second line layer formed on the first insulating layer;
 - a second insulating layer formed on the substrate, having respective contact holes therein located at the first and second line layers;
 - a third line layer formed on the second insulating layer;
 - a passivation layer formed on the substrate, having respective contact holes therein located at the first, second and third line layers; and
 - a pixel electrode on the passivation layer to electrically connect the first, second and third line layers through each contact hole.
2. (Original) The LCD device as claimed in claim 1, wherein the first line layer is formed of the same material as a gate line.
3. (Original) The LCD device as claimed in claim 1, wherein the first line layer is formed as a double-layered structure inclusive of an AlNd alloy and Mo.

4. (Original) The LCD device as claimed in claim 1, wherein the second line layer is formed of the same material as a data line.

5. (Original) The LCD device as claimed in claim 1, wherein the second line layer is formed of Cr.

6. (Original) The LCD device as claimed in claim 1, wherein the third line layer is formed of the same material as a reflective layer.

7. (Original) The LCD device as claimed in claim 1, wherein the third line layer is formed of an AlNd alloy.

8. (Original) The LCD device as claimed in claim 1, wherein the LCD device is a reflective LCD device.

9. (Original) The LCD device as claimed in claim 1, wherein the LCD device is a transreflective LCD device.

10. (Original) The LCD device as claimed in claim 1, wherein the first insulating layer is formed on an entire surface of the substrate.

11. (Original) The LCD device as claimed in claim 1, wherein the second insulating layer is formed on an entire surface of the substrate.

12. (Original) The LCD device as claimed in claim 1, wherein the passivation layer is formed on an entire surface of the substrate.

13. (Currently Amended) A method for manufacturing an LCD device having a cell array region and an input line part comprising the steps of:

~~forming a gate line on a substrate of the cell array region, simultaneously, and a first line layer on the substrate at the input line part;~~

forming a first insulating layer on ~~a~~ the substrate;

forming a semiconductor layer on the first insulating layer of the cell array region;

forming a data line having source and drain electrodes at both sides of the semiconductor layer of the cell array region, simultaneously, and a second line layer on the first insulating layer of the input line part;

forming a second insulating layer on the substrate;

forming a reflective layer on the second insulating layer of the cell array region, simultaneously, and a third line layer on ~~a third the second~~ insulating layer of the input line part;

forming a passivation layer on the substrate;

forming respective contact holes to expose the drain electrode ~~of the cell array region,~~ and surfaces of the first, second ~~the and~~ third line layers ~~of the input line part;~~ and

forming a pixel electrode ~~to connect the passivation layer of the cell array region to on the passivation layer to electrically connect the drain electrode and the first, second and third line layers through the contact holes.~~

14. (Original) The method as claimed in claim 13, wherein the LCD device is a reflective LCD device.

15. (Original) The method of as claimed in claim 13, wherein the LCD device is a transflective LCD device.

16. (Original) The method as claimed in claim 13, wherein the first insulating layer is formed on an entire surface of the substrate.

17. (Original) The method as claimed in claim 13, wherein the second insulating layer is formed on an entire surface of the substrate.

18. (Original) The method as claimed in claim 13, wherein the passivation layer is formed on an entire surface of the substrate.